

Title (en)
LITHOGRAPHY SYSTEM ARRANGED ON A FOUNDATION, AND METHOD FOR ARRANGING A LITHOGRAPHY SYSTEM ON SAID FOUNDATION

Title (de)
AUF EINEM UNTERGRUND ANGEORDNETES LITHOGRAFIESYSTEM UND VERFAHREN ZUR ANORDNUNG EINES LITHOGRAFIESYSTEMS AUF DIESEM UNTERGRUND

Title (fr)
SYSTÈME LITHOGRAPHIQUE AGENCÉ SUR UNE FONDATION, ET PROCÉDÉ POUR L'AGENCEMENT D'UN SYSTÈME LITHOGRAPHIQUE SUR LADITE FONDATION

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Abstract (en)
[origin: WO2012039606A1] The invention relates to a vibration isolation requiring system, such as a lithography system, arranged on a foundation (100), for example part of the floor in the room where the lithography system is arranged, and a method for arranging a lithography system on a foundation. The lithography system is arranged on top of a rigid or solid base plate (110), wherein said base plate having one or more struts (150) attached thereto for placing the lithography system onto the foundation, wherein the one or more struts are arranged at a side of the base plate facing the foundation, and wherein the base plate is provided with a cut-out or an opening for mounting equipment (330) underneath a vacuum chamber of the lithography system.

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